



PRESS RELEASE

2011 International Conference on Frontiers of Characterization and Metrology for Nanoelectronics Set for May 23-26 in Grenoble

MINATEC Innovation Campus Is IC-FCMN's First Conference Venue Outside U.S.

GRENOBLE, France – Feb. 17, 2011 – The International Conference on Frontiers of Characterization and Metrology for Nanoelectronics 2011 (IC-FCMN 2011) will be May 23-26 at MINATEC, an international center for micro- and nanotechnologies, in Grenoble, France.

The 8th annual conference, which is being held for the first time outside the United States, will attract participants from around the world to examine the latest advances in characterization and metrology that will help shape the future of the nanoelectronics revolution.

The conference will include more than two dozen invited papers.

IC-FCMN 2011 will allow extended interaction between characterization and metrology experts and users from industry and R&D labs. By providing an opportunity for attendees to share results and interests, the conference also will facilitate new research partnerships and help establish a common vision for meeting nanoelectronics characterization and metrology challenges.

The conference formerly was called "Characterization and Metrology for ULSI Technology."

For more information and registration, visit www.nist.gov/pml/semiconductor/conference/

About CEA-Leti

CEA is a French research and technology organisation, with activities in four main areas: energy, information technologies, healthcare technologies and defence and security. Within CEA, the Laboratory for Electronics & Information Technology (CEA-Leti) works with companies in order to increase their competitiveness through technological innovation and transfers. CEA-Leti is focused on micro and nanotechnologies and their applications, from wireless devices and systems, to biology and healthcare or photonics. Nanoelectronics and microsystems (MEMS) are at the core of its activities. As a major player in MINATEC campus, CEA-Leti operates 8,000-m² state-of-the-art clean rooms, on 24/7 mode, on 200mm and 300mm wafer standards. With 1,200 employees, CEA-Leti trains more than 190 Ph.D. students and hosts 200 assignees from partner companies. Strongly committed to the creation of value for the industry, CEA-Leti puts a strong emphasis on intellectual property and owns more than 1,700 patent families. For more information, visit www.leti.fr.

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